

## ABSTRACT OF THE DISCLOSURE

A single crystal M\*N article, which may be made by a process including the steps of: providing a substrate of material having a crystalline surface which is epitaxially compatible with M\*N; depositing a layer of single crystal M\*N over the surface of the substrate; and removing the substrate from the layer of single crystal M\*N, e.g., with an etching agent which is applied to the substrate to remove same, to yield the layer of single crystal M\*N as said single crystal M\*N article. The bulk single crystal M\*N article is suitable for use as a substrate for the fabrication of microelectronic structures thereon, to produce microelectronic devices comprising bulk single crystal M\*N substrates, or precursor structures thereof.